Inventor: Cem Basceri et. al.

Title: Circuit Constructions

Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional application of U.S. Patent Application Serial No. 10/443,354, which was filed May 21, 2003, which is a continuation-in-part application of U.S. Patent Application Serial No. 10/243,386, filed September 13, 2002; which is a divisional application of U.S. Patent Application Serial No. 09/827,759, filed April 6, 2001 and now U.S. Patent Number 6,511,896. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: <u>3/25/2004</u> Attorney:

David G. Latwesen, Ph.D.

Reg. #38,533

WELLS ST. JOHN P.S.

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Form PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE								ATTY, DOCKET NO. MI22-2515				PRIORITY SERIAL NO. 10443,354		
LIST OF ART CITED BY APPLICANT (Use several sheets if nocessary)								APPLICANT Cem Basceri et al.						
								PRIORITY FILING DATE May 21, 2003				PRIORITY GROUP		
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EXAMINER DATE CONSIDERED														
*EXAMINER: Ir communication to	itial if references	ence consid	dered, whether or not citat	ion is in conformat	nce with MPEP 609); Draw line through citati	lion if	f not in conformance and	not considered	l. Inch	ude copy o	f this form with	next	